

含硫、磷配位基之單核鈷和混價雙核鈷的製備和反應性探討

摘要：

文獻中提到 Co^{II} 有機會與氧氣反應形成 Co^{III} 超氧再形成過氧。[1]

本實驗室先前合成 $[\text{PPN}][\text{Mn}^{\text{II}}(\text{TMSPS}_3)(\text{DABCO})]$ 加入氧氣後可形成 $[\text{PPN}][\text{Mn}^{\text{IV}}(\text{O}_2)(\text{TMSPS}_3)]$ 。[2]

我們嘗試將中心金屬換成 Co ，合成出 $\text{Co}^{\text{II}}-\text{DABCO}$ 、 $\text{Co}^{\text{III}}-\text{R}$ ($\text{R}=\text{DABCO}$ 、 Cl)以及 $\text{Co}^{\text{II}}-\text{Co}^{\text{III}}$ ，其配位環境皆為 TMSPS_3 [3]。

實驗與結果：

合成 $[\text{PPN}][\text{Co}^{\text{II}}(\text{DABCO})\text{TMSPS}_3]$ 、 $\text{Co}^{\text{III}}(\text{DABCO})\text{TMSPS}_3$

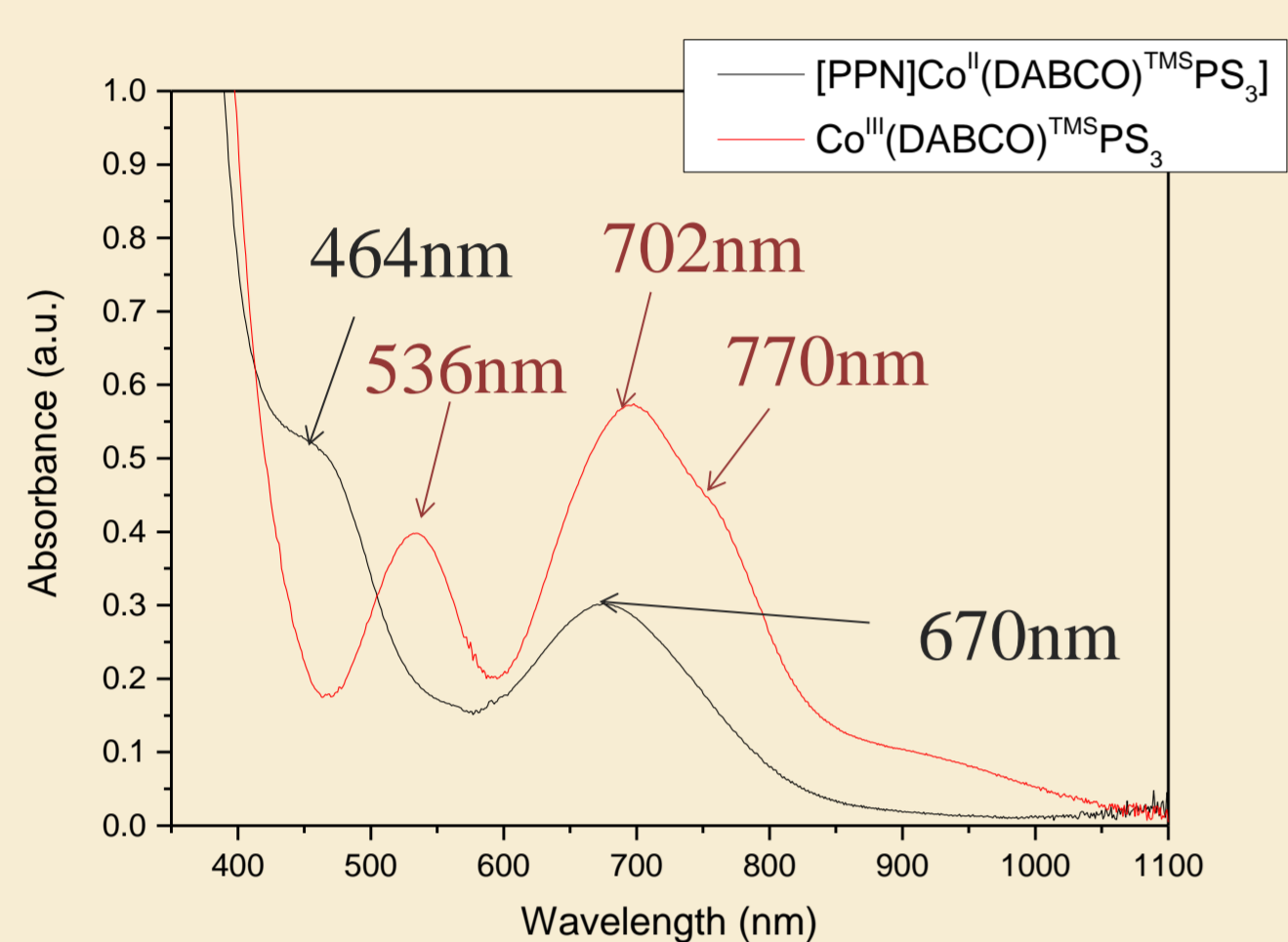
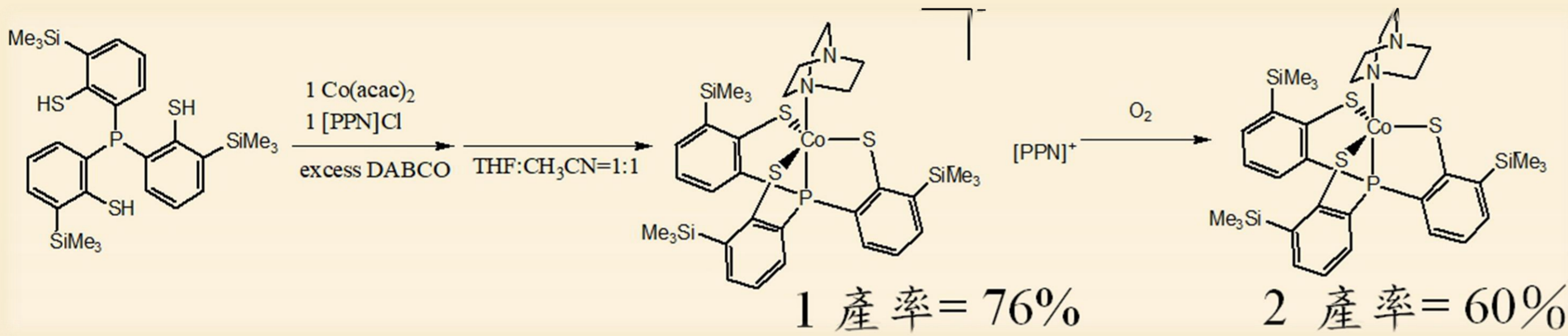


圖1 UV-Vis 光譜圖_1(黑)、2(紅)

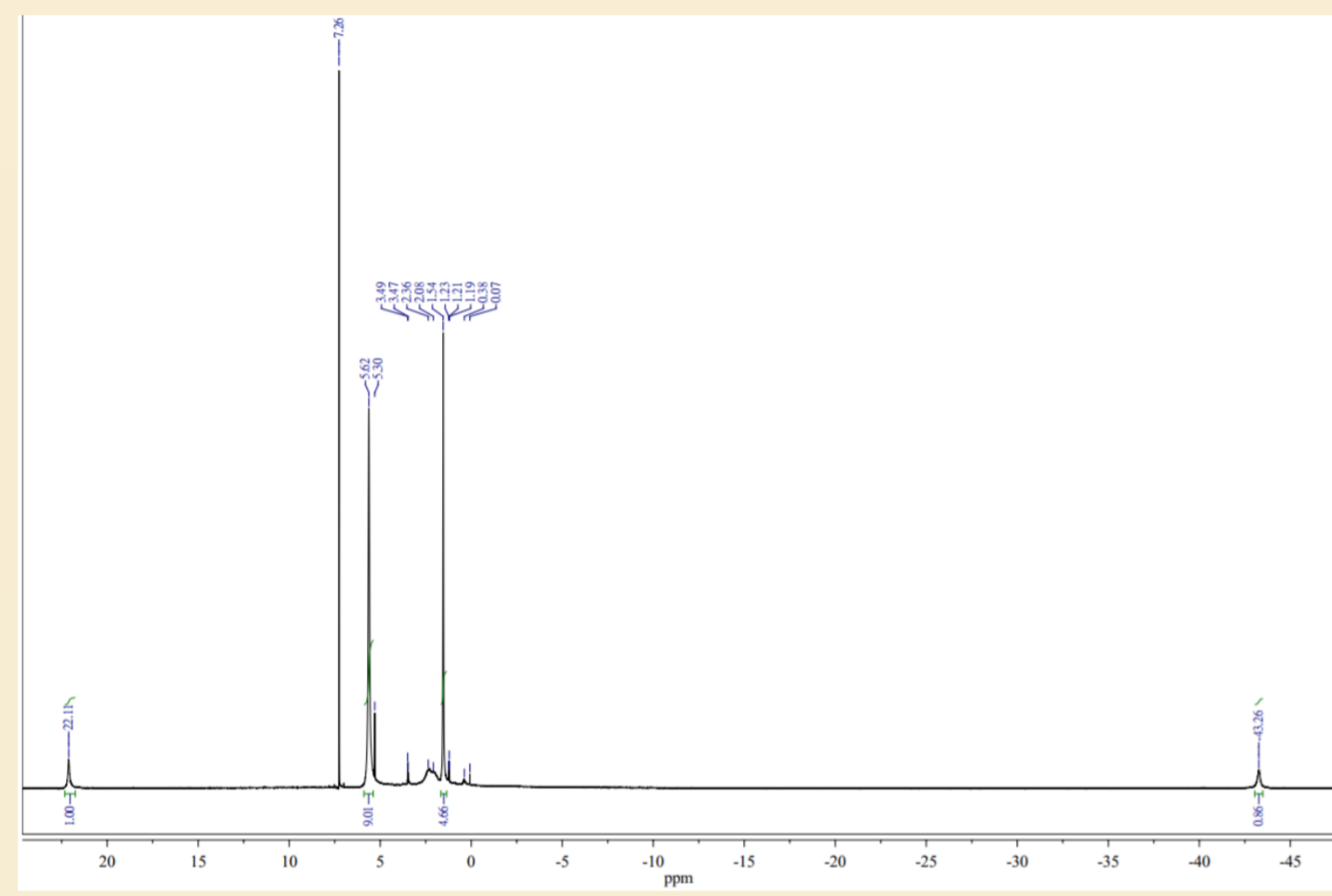


圖2 $^1\text{H-NMR}$ 光譜圖_2 in CDCl_3

合成 $[\text{PPN}][\text{Co}^{\text{II}}\text{Co}^{\text{III}}(\text{TMSPS}_3)_2]$

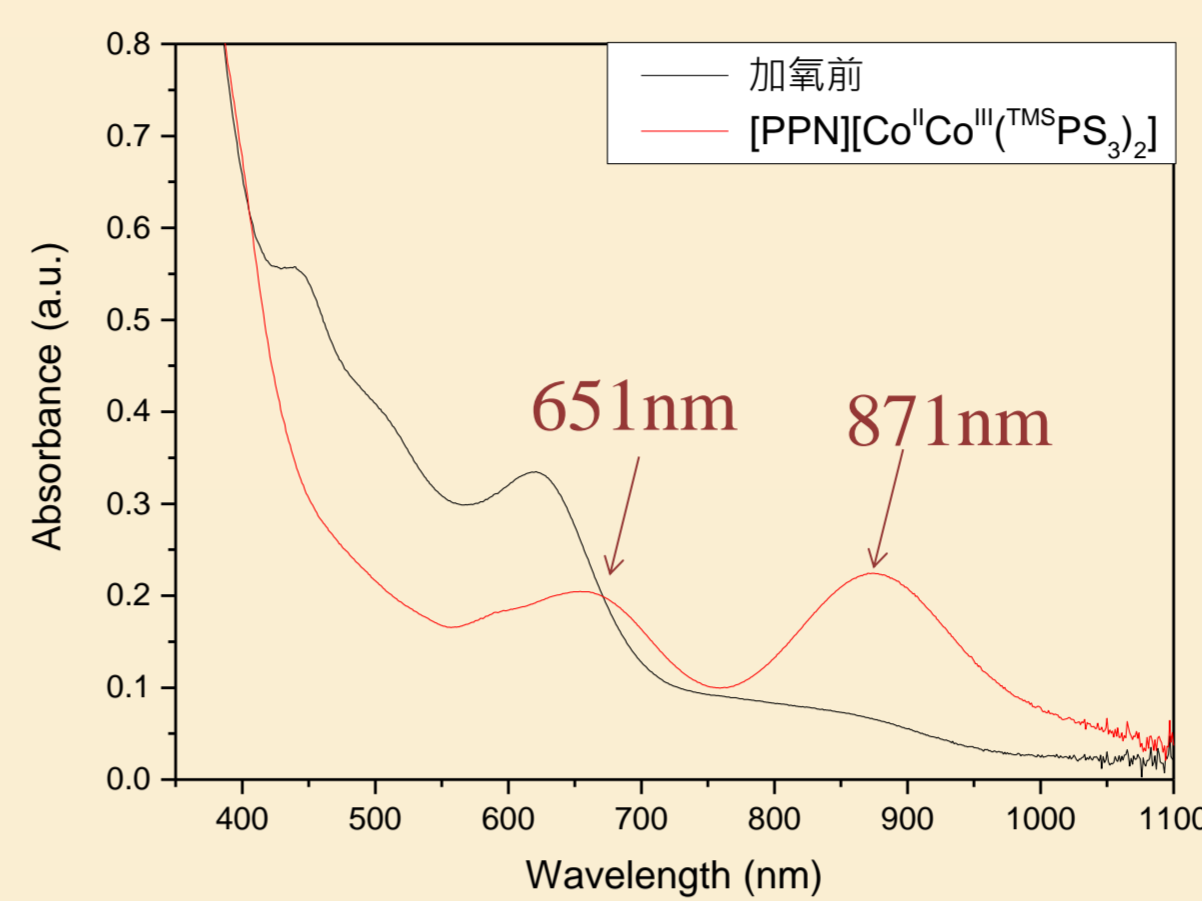
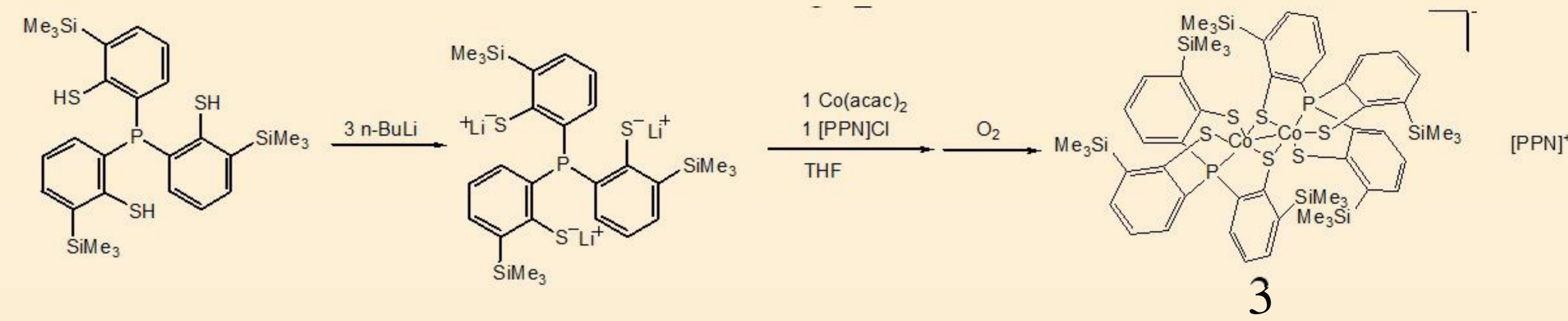


圖6 UV-Vis 光譜圖_3(紅)

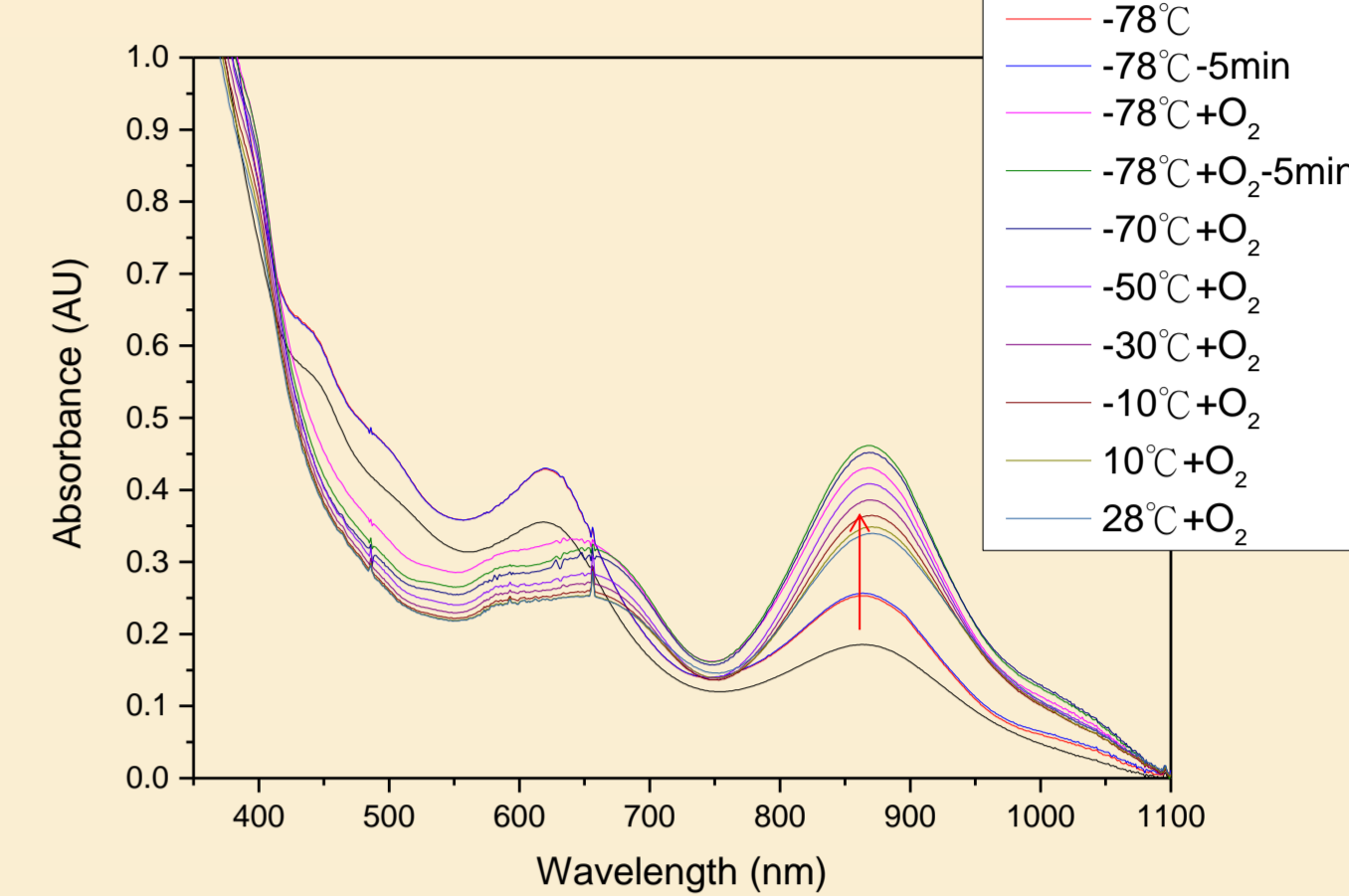


圖7 UV-Vis 光譜圖_3於-78°C加 O_2

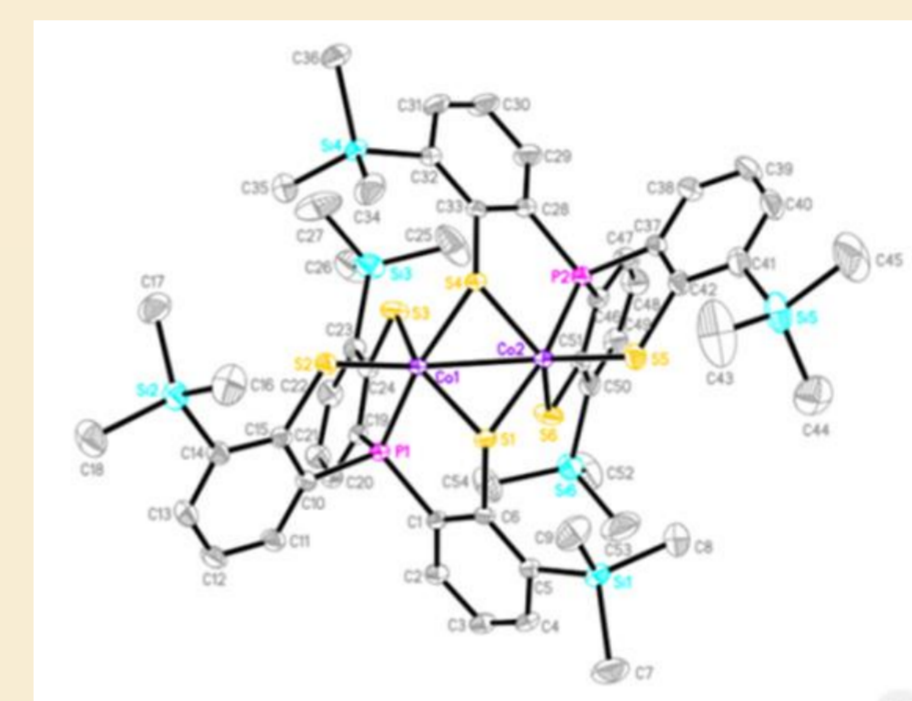


圖8 X-ray 晶體結構圖_3

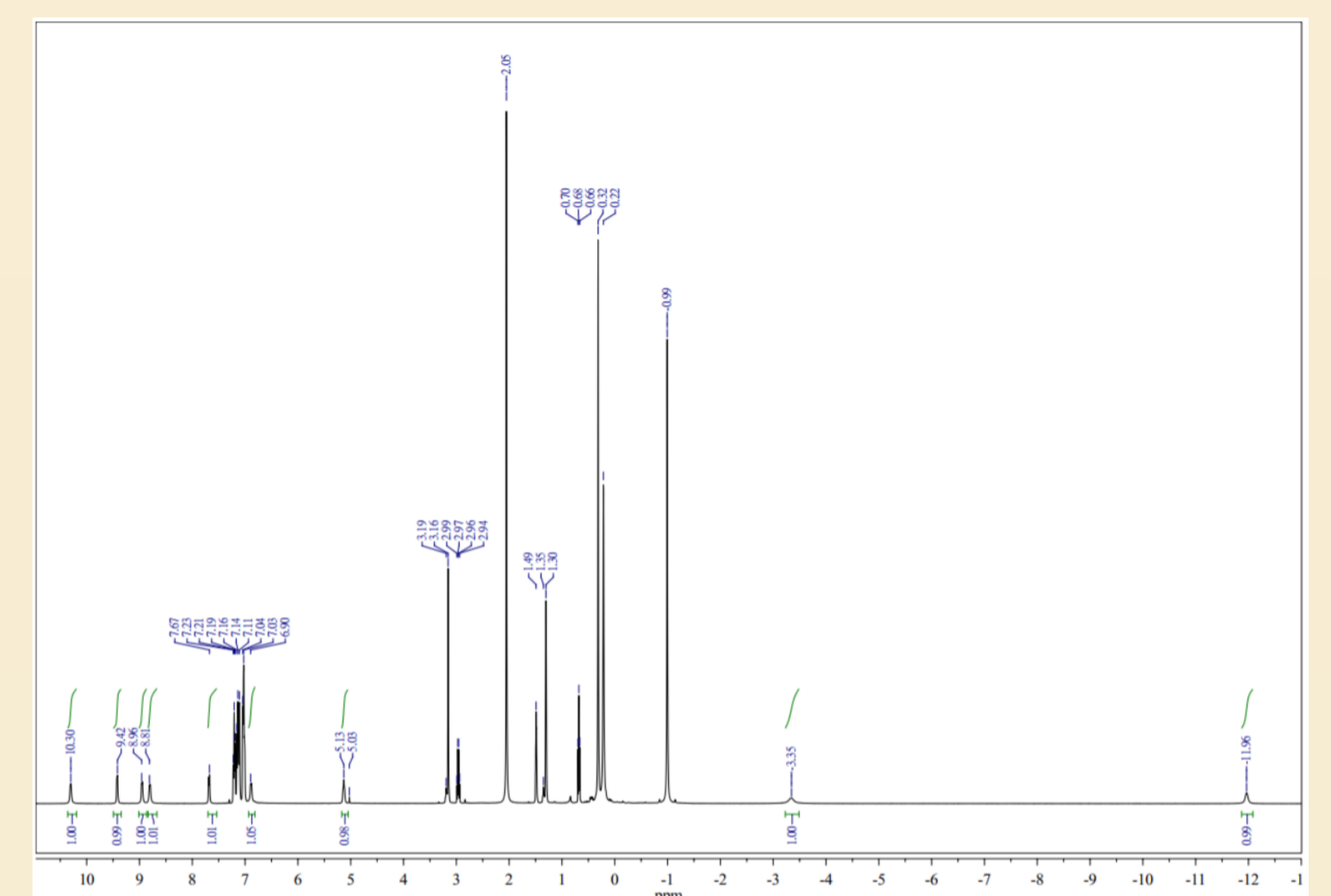


圖9 $^1\text{H-NMR}$ 光譜圖_3 in $\text{CD}_3\text{CN}+\text{d}_8\text{-THF}$

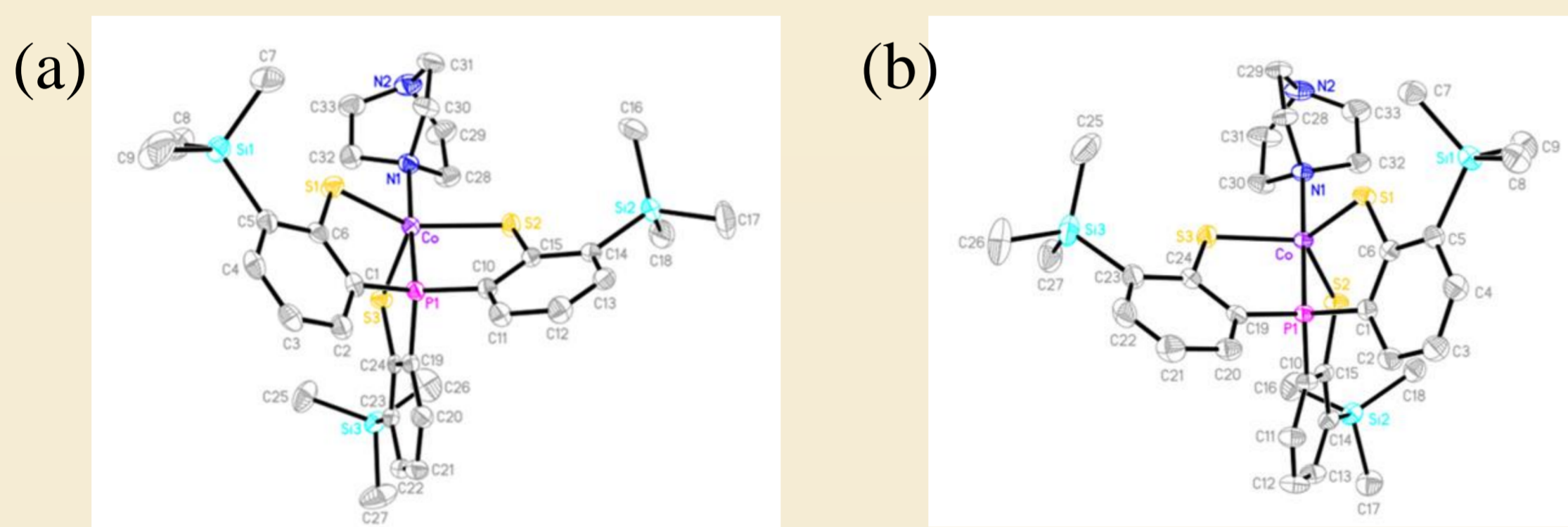


圖3 X-ray 晶體結構圖_(a)1 (b)2

Co 和相鄰元素的鍵長[Å]

	1	2
Co-N(1)	2.067(3)	2.068(2)
Co-P(1)	2.0973(9)	2.1395(7)
Co-S(1)	2.2762(9)	2.2331(7)
Co-S(2)	2.2956(9)	2.2371(7)
Co-S(3)	2.3445(8)	2.2421(8)

製備 $[\text{PPN}][\text{Co}^{\text{III}}(\text{Cl})\text{TMSPS}_3]$

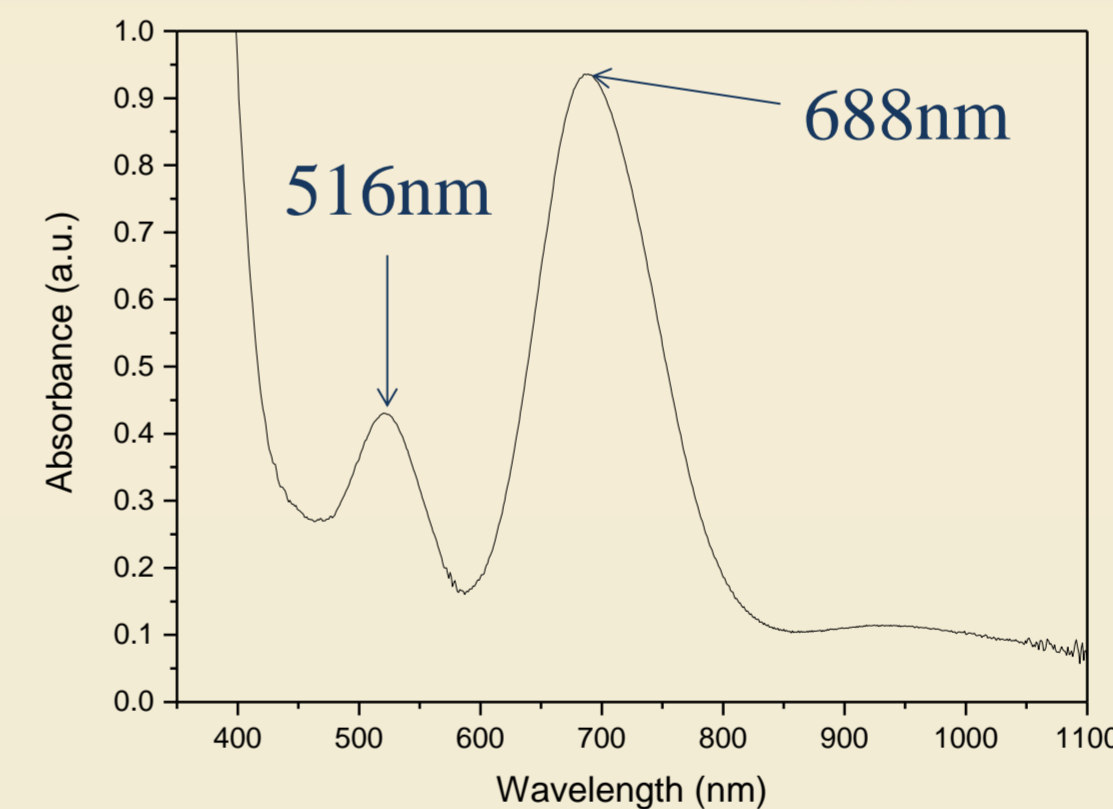
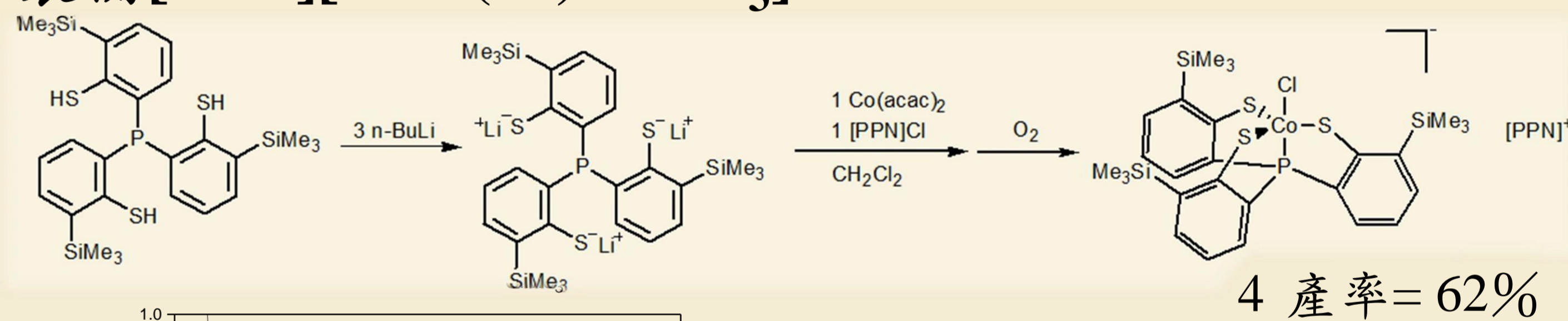


圖10 UV-Vis 光譜圖_4

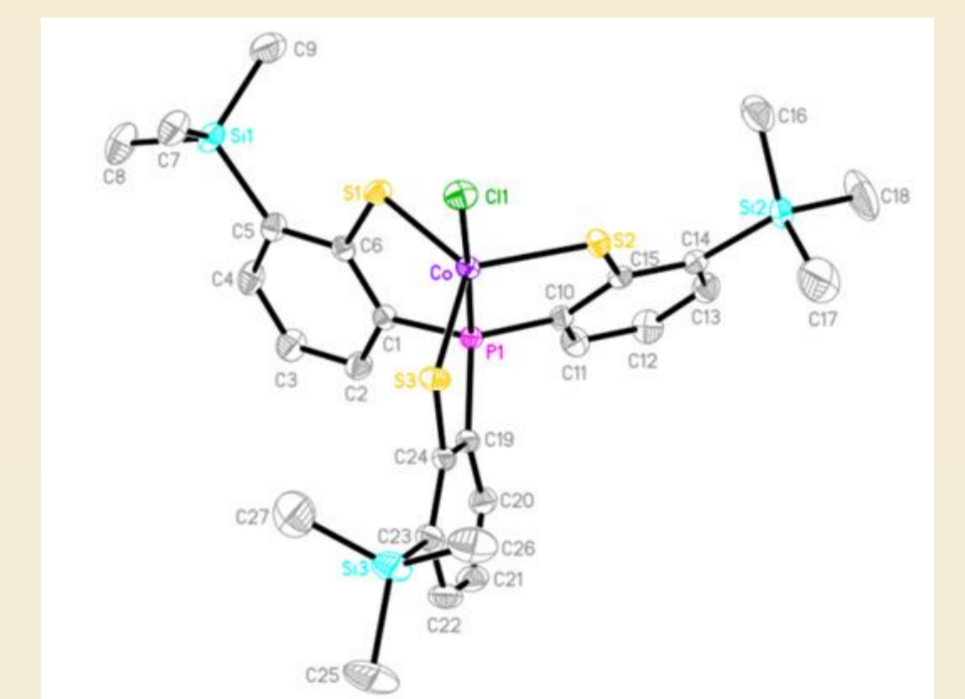


圖12 X-ray 晶體結構圖_4

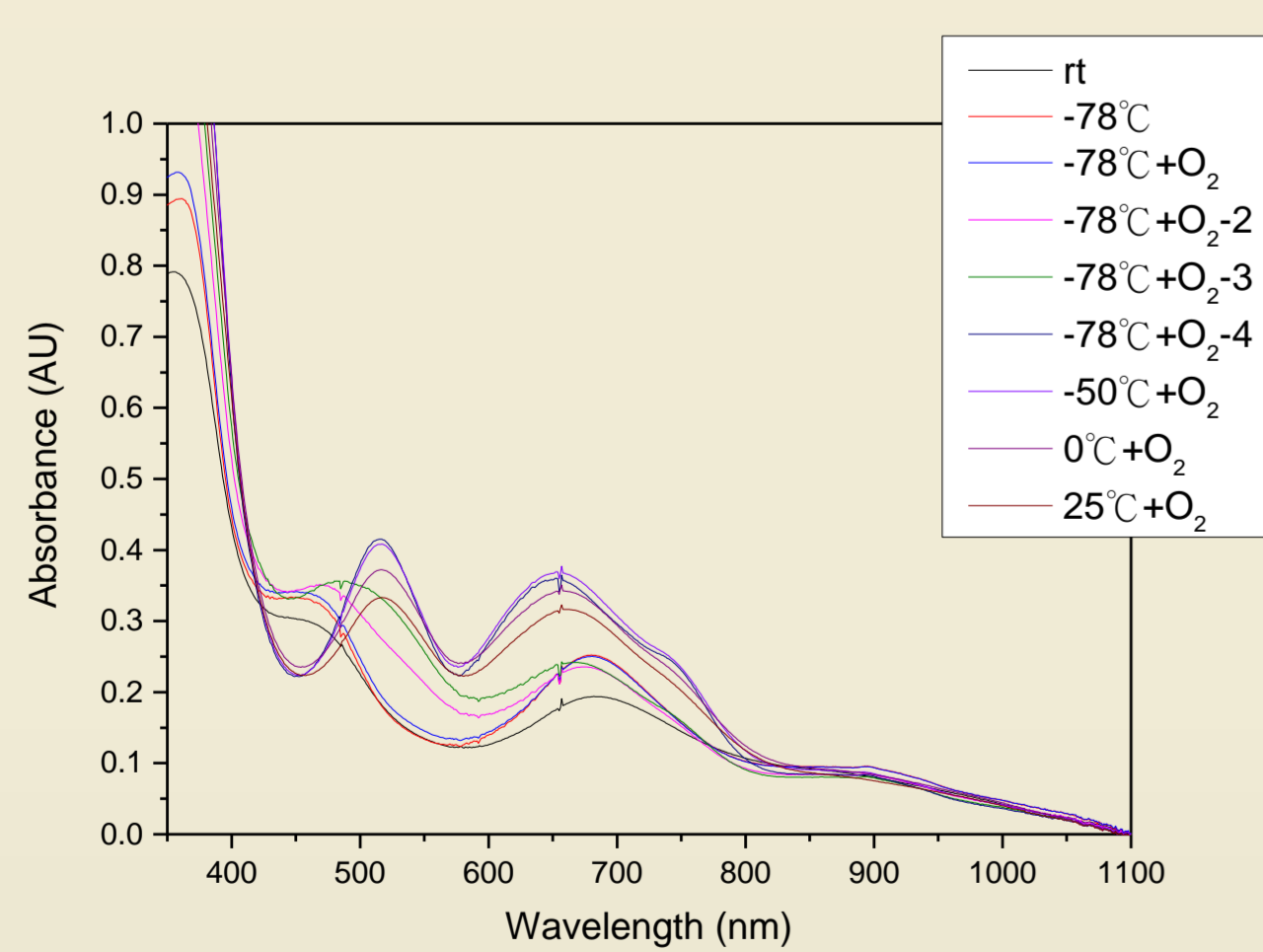


圖4 UV-Vis光譜圖_1於-78°C加 O_2

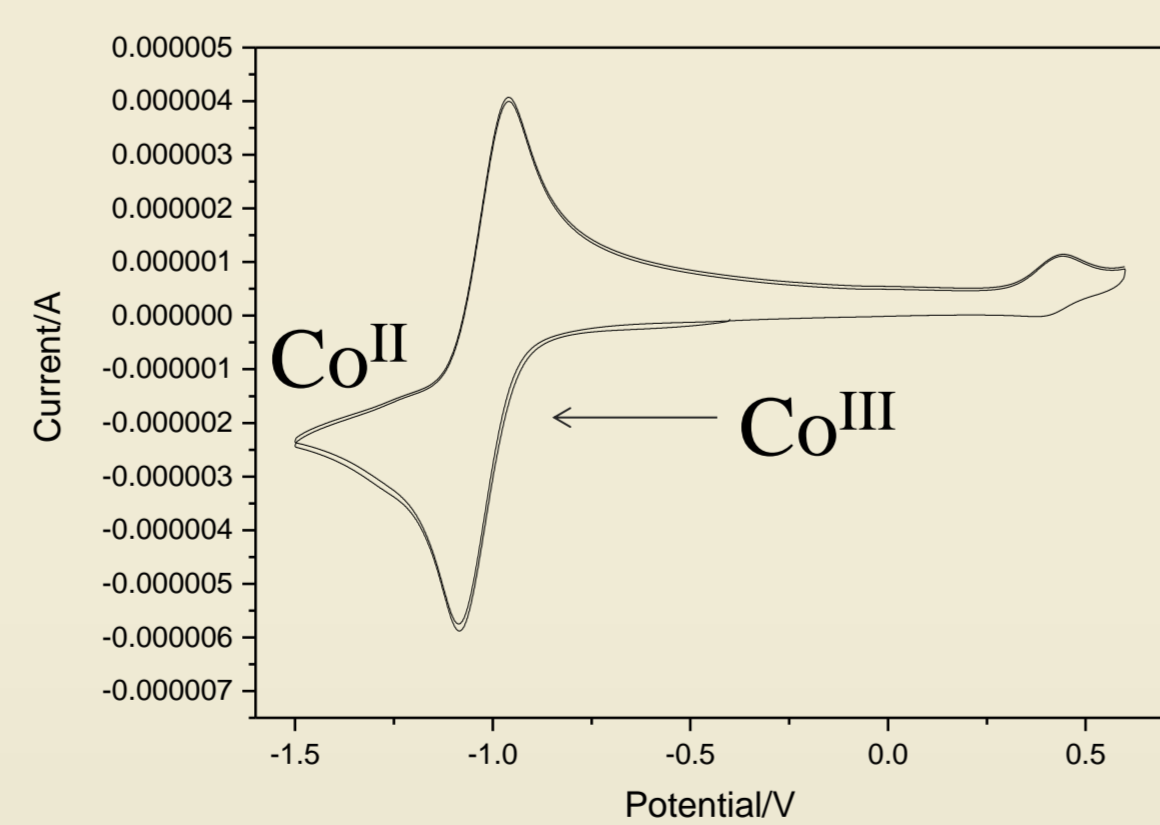


圖5 CV光譜圖_1

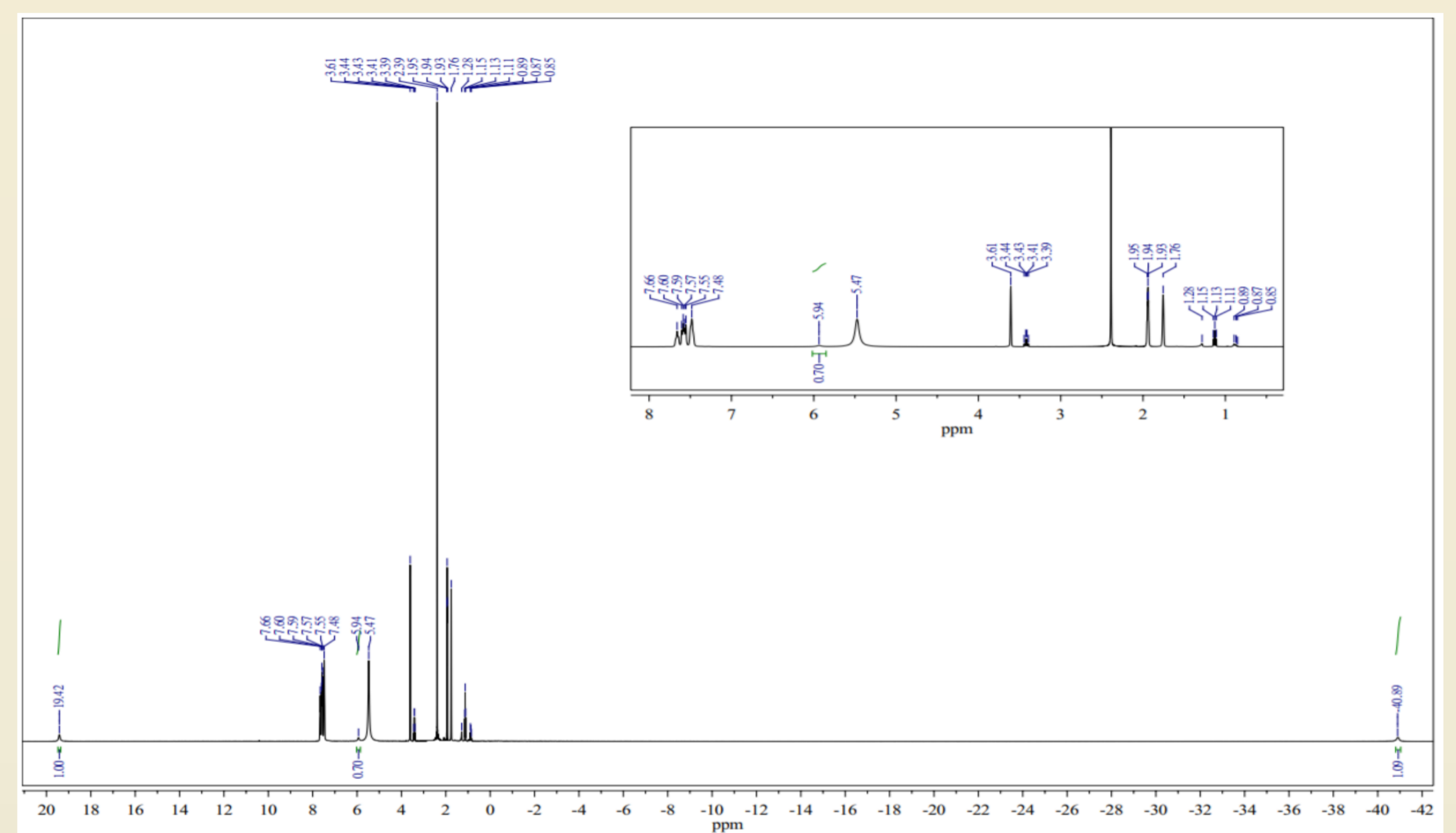


圖13 $^1\text{H-NMR}$ 光譜圖_4 in $\text{CD}_3\text{CN}+\text{d}_8\text{-THF}$

結論：

本實驗用 TMSPS_3 為配位基合成出了3種單核鈷錯合物以及1種混價雙核鈷錯合物，都有良好的產率，並藉由光譜來鑑定其性質。

$\text{Co}^{\text{III}}(\text{DABCO})\text{TMSPS}_3$ 藉由循環伏安法測定，發現 Co^{III} 可還原為 Co^{II} ，再由 Co^{II} 氧化為 Co^{III} ，形成一個可逆氧化還原。將 $[\text{PPN}][\text{Co}^{\text{II}}(\text{DABCO})\text{TMSPS}_3]$ 與 $[\text{PPN}][\text{Co}^{\text{II}}\text{Co}^{\text{III}}(\text{TMSPS}_3)_2]$ 氧化前化合物於-78°C下加入氧氣，皆沒有發現中間體的存在。

參考文獻：

- [1] Lee, C. M.; Wu, W. Y.; Chiang, M. H.; Bohle, D. S.; Lee, G. H. *Inorg. Chem.* **2017**, *56*, 10559.
- [2] Wang, C. C.; Chang, H. C.; Lai, Y. C.; Fang, H.; Li, C. C.; Hsu, H. K.; Li, Z. Y.; Lin, T. S.; Kuo, T. S.; Neese, F.; Ye, S.; Chiang, Y. W.; Tsai, M. L.; Liaw, W. F.; Lee, W. Z. *J. Am. Chem. Soc.* **2016**, *138*, 1418.
- [3] Block, E.; Ofori-Okai, G.; Zubietta, J. *J. Am. Chem. Soc.* **1989**, *111*, 2327